

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	0	"50772905".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 15:28
S2	2	"5772905".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 15:41
S3	530	step and flash and wilson.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 15:41
S4	23	step adj3 flash and wilson.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 16:34
S5	0	nanoimprint and S4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 15:54
S6	76	imprint adj2 lithography with step adj2 flash	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27
S7	0	imprint adj2 lithography and (nqd dnq dq) adj2 (photoresist photosensitive novolak novolac)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:10
S8	0	imprint adj2 lithography and (nqd dnq dq diazoquinone diazonaphthoquinone naphthoquinonediazide quinonediazide diazide diazido naphthoquinonediazido) adj2 (photoresist photosensitive novolak novolac)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:11
S9	19	imprint adj2 lithography with (photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:21
S10	5	imprint adj2 lithography and 430/326, 325.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:26
S11	0	mold with sputter adj2 deposit same (grinding grind)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:28

S12	0	(mold moldboard )with (sputter sputtering) adj2 deposit same (grinding grind)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:28
S13	0	(mold moldboard ) with (sputter sputtering) adj2 deposit same (grinding grind)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:29
S14	1	(mold moldboard ) same (sputter sputtering) adj2 deposit	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:29
S15	1	liao-weng-chung.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:30
S16	3	hsu-lien-chung.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:30
S17	3	lee-po-i.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:30
S18	3	hon-min-hsiung.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:30
S19	1	hong-chau-nan.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/23 18:31
S20	7	S16 S17 S18	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27
S21	3	hsu-lien-chung.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27
S22	3	lee-po-i.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27
S23	3	hon-min-hsiung.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27

S24	7	S21 S22 S23	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27
S25	106	imprint adj2 lithography with step adj2 flash	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:27
S26	1	S24 and S25	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:32
S27	115	imprint with optical with lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 04:19
S28	36	S27 and nanoimprint adj2 lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:33
S29	33	S28 and @ad<"20040220"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 02:33
S30	7	imprint adj2 lithography and (grind cmp) with (mask imprint adj2 mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 10:29
S31	5	S30 and @ad<"20040220"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/10/31 10:30